

TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT Under 37 CFR 1.97(b), (c), or (d)			Docket No. 8327/ETCH/SILICON
In re Application of: Mui, et al.			
Serial No. 10/690,318	Filing Date October 21, 2003	Examiner	Group Art Unit
Title: METHOD FOR CONTROLLING ACCURACY AND REPEATABILITY OF AN ETCH PROCESS			

Address to:
**Commissioner for Patents
Alexandria, VA 22313-1450**

37 CFR 1.97(b)

1. ☒ The Information Disclosure Statement submitted herewith is being filed within three months of the filing of a national application other than a continued prosecution application under 37 CFR 1.53(d); within three months of the date of entry of the national stage as set forth in 37 CFR 1.491 in an international application; before the mailing of a first Office Action on the merits; or before the mailing of a first Office Action after the filing of a request for continued examination under 37 CFR 1.114.

37 CFR 1.97(c)

2. ☐ The Information Disclosure Statement submitted herewith is being filed after the period specified in 37 CFR 1.97(b), but prior to the mailing date of a Final Action under 37 CFR 1.113, a Notice of Allowance under 37 CFR 1.311, or an Action that otherwise closes prosecution in the application, and is accompanied by the statement or fee as indicated below.

37 CFR 1.97(d)

3. ☐ The Information Disclosure Statement submitted herewith is being filed after the period specified in 37 CFR 1.97(c), but on or before payment of the issue fee and is accompanied by the statement and fee as indicated below.

Required Statements and/or Fees Under 37 CFR 1.97(c) or (d)

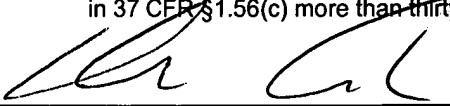
☐ Each item of information contained in the accompanying Information Disclosure Statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the Information Disclosure Statement. (37 CFR 1.97(e)(1))

☐ No item of information in the accompanying Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the undersigned person, after making reasonable inquiry, no item of information contained in the accompanying Information Disclosure Statement was known to any individual designated in 37 CFR 1.56(c) more than three months prior to the filing of the Information Disclosure Statement. (37 CFR 1.97(e)(2))

☐ The fee set forth in 37 CFR 1.17(p). Please credit any overpayment or charge any insufficiencies to deposit account number 20-0782.

37 CFR §1.704(d)

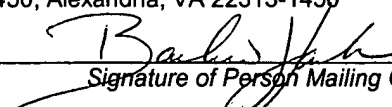
4. ☐ Each item of information in the accompanying Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart application and this communication was not received by any individual designated in 37 CFR §1.56(c) more than thirty days prior to the filing of the Information Disclosure Statement.


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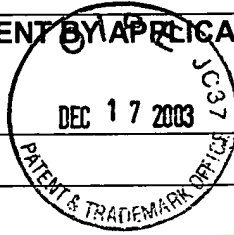
Dated: Dec 12, 2003

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I certify that this document is being deposited on 12-15-2003 with the U.S. Postal Service as first class mail under 37 CFR §1.8 and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450


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U.S. Department of Commerce, Patent and Trademark Office		Docket No.	Serial No.
(PTO Form 1449 modified)		8327/ETCH/SILICON	10/690,318
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant Mui, et al.	Confirmation No.:
(Use several sheets if necessary)		Filing Date	Group
Examiner			

**U.S. Patent Documents**

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
	A1	2002/0171828	11/21/2002	Cohen et al.	356	328	07/01/2002
	A2	2002/0072003	06/13/2002	Brill et al.	430	30	10/30/2001
	A3	2003/0000922	01/02/2003	Subramanian et al.	216	60	06/27/2001
	A4	5,926,690	07/20/1999	Toprac et al.	438	17	
	A5	5,948,203	09/07/1999	Wang	156	345	
	A6	6,161,054	12/12/2000	Rosenthal et al.	700	121	
	A7	6,245,581	06/12/2001	Bonser et al.	438	8	
	A8	6,424,417	07/23/2002	Cohen et al.	356	388	
	A9	6,479,309	11/12/2002	Wright	438	16	
	A10	6,486,492	11/26/2002	Su	257	48	
	A11	6,501,555	12/31/2002	Ghandchari et al.	356	630	

Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
	B1	03/003447	01/09/2003	WIPO	H01L	21/66	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B2						<input type="checkbox"/>	<input type="checkbox"/>

OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
	C1	Lee, et al., "Analysis of Reflectometry and Ellipsometry Data from Patterned Structures," Characterization and Metrology for UCSI Technology: 1998 International Conference, Seiler, et al., eds., pg 331-335
	C2	Raymond, "Angle-resolved scatterometry for semiconductor manufacture," Microlithography World, Winter 2000.
	C3	Toprac, A., "AMD's Advanced Process Control of Ply-Gate Critical Dimension," Proc. SPIE Vol 3882, pg 62-65, Sept, 1999.
	C4	Yang, et al., "Line-profile and Critical Dimension Measurements Using a Normal Incidence Optical Metrology System," Proceedings of SPIE Vol. 4689, March 2002,

Examiner

Date Considered

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.